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Applicant: BAKKER et al.

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Date: November 21, 2003

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### U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR						
BR						
CR						
DR						
ER						
FR						
GR						
HR						
IR						
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KR						
LR						
MR						
NR						
OR						

### FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
HN	PR EP 1 182 510 A1	02/2002	Europe	MOORS et al.	X			
	QR							
	RR							
	SR							
	TR							
	UR							
	VR							

OTHER (Including in this order: Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

HN	WR	Nguyen et al., "Imaging of extreme ultraviolet lithographic masks with programmed substrate defects," J. Vac. Sci. Technol. B 12(6):3833-3840, XP-002096163 (1994)						
	XR							
	YR							
	ZR							
	AAR							
	BBR							
	CCR							

Examiner H. Nguyen Date Considered: 8/4/2004

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.